

## ABSTRACT OF DISCLOSURE

A substrate-cleaning apparatus includes a transmission unit, a wet cleaning unit and a dry cleaning unit. The transmission unit includes a movable clamp for clamping a substrate that includes a face without covering the face of the substrate. The wet cleaning unit includes a wiper and a liquid pump. The wiper includes a strip of cleaning cloth and an abutting element for pressing the cleaning cloth against the face of the substrate. The liquid pump sends cleaning liquid to the abutting element that in turn sends the cleaning liquid to the cleaning cloth when the abutting element presses the cleaning cloth against the face of the substrate. The dry cleaning unit includes a wiper comprising a strip of cleaning cloth for wiping dry the face of the substrate without leaving any water mark on the face.

Figure 2